

**Notice of References Cited**

Application/Control No.

10/543,141

Applicant(s)/Patent Under  
Reexamination  
AIZAWA ET AL.

Examiner

MARIANNE L. PADGETT

Art Unit

1792

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-5,272,015 A	12-1993	Hamdi et al.	428/472
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N	DE 198 15 019 A1	10-1999	Germany	Naumann et al.	C23C 8/24
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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Kim et al., Derwent abstract ACC-No.2001-548299 of Korean publication KR 200102 8157, published 4/6/2001, titled "method for preparing aluminum nitride by using plasma and device thereof", classification C01F 7/66
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	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.